

IN THE CLAIMS

Please amend the claims as follows:

Claim 1 (Currently Amended): A high dispersible hydrophobic fine silica powder, wherein

hydrophobicity is more than 50%, and

triboelectrostatic charge to an iron powder is more than -500 μ C/g, and

~~decomposition rate of an organic group on the powder surface is less than 15%.~~

Claim 2 (Original): The high dispersible hydrophobic fine silica powder according to claim 1, wherein transmittance of a 5% alcoholic dispersion liquid is more than 40%.

Claim 3 (Currently Amended): The high dispersible hydrophobic fine silica powder of claim 1, wherein said high dispersible hydrophobic fine silica powder is synthesized by a vapor phase method, and has a specific surface area of more than 200 m^2/g by the BET method and an amount of residual hydrochloride of less than 100 ppm.

Claims 4-5 (cancelled).

Claim 6 (Currently Amended): The high dispersible hydrophobic fine silica powder of claim 2, wherein said high dispersible hydrophobic fine silica powder is synthesized by a vapor phase method, and has a specific surface area of more than 200 m^2/g by the BET method and an amount of residual hydrochloride of less than 100 ppm.

Claim 7 (Previously Presented): A production method of the high dispersible hydrophobic fine silica powder according to claim 1, wherein a hydrophobic agent comprising a volatile organic silicon compound is mixed in the gas state with a fine silica powder in a fluidized bed type reaction vessel at the time of a hydrophobic treatment, and a gas flow rate at the time of this mixing is more than 5.0 cm/sec.

Claim 8 (Previously Presented): A production method of the high dispersible hydrophobic fine silica powder according to claim 2, wherein a hydrophobic agent comprising a volatile organic silicon compound is mixed in the gas state with a fine silica powder in a fluidized bed type reaction vessel at the time of a hydrophobic treatment, and a gas flow rate at the time of this mixing is more than 5.0 cm/sec.

Claim 9 (Previously Presented): A production method of the high dispersible hydrophobic fine silica powder according to claim 3, wherein a hydrophobic agent comprising a volatile organic silicon compound is mixed in the gas state with a fine silica powder in a fluidized bed type reaction vessel at the time of a hydrophobic treatment, and a gas flow rate at the time of this mixing is more than 5.0 cm/sec.

Claim 10 (Previously Presented): A production method of the high dispersible hydrophobic fine silica powder according to claim 6, wherein a hydrophobic agent comprising a volatile organic silicon compound is mixed in the gas state with a fine silica powder in a fluidized bed type reaction vessel at the time of a hydrophobic treatment, and a gas flow rate at the time of this mixing is more than 5.0 cm/sec.

Claim 11 (Currently Amended): [[A]] The production method of the high dispersible hydrophobic fine silica powder according to claim 7 ~~claim 1~~, wherein [[the]] a gas flow rate in the fluidized bed type reaction vessel is more than 3.0 cm/sec at the time of the hydrophobic treatment.

Claim 12 (Currently Amended): [[A]] The production method of the high dispersible hydrophobic fine silica powder according to claim 8 ~~claim 2~~, wherein [[the]] a gas flow rate in the fluidized bed type reaction vessel is more than 3.0 cm/sec at the time of the hydrophobic treatment.

Claim 13 (Currently Amended): [[A]] The production method of the high dispersible hydrophobic fine silica powder according to claim 9 ~~claim 3~~, wherein [[the]] a gas flow rate in the fluidized bed type reaction vessel is more than 3.0 cm/sec at the time of the hydrophobic treatment.

Claim 14 (Currently Amended): [[A]] The production method of the high dispersible hydrophobic fine silica powder according to claim 10 ~~claim 6~~, wherein [[the]] a gas flow rate in the fluidized bed type reaction vessel is more than 3.0 cm/sec at the time of the hydrophobic treatment.